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Substitute for form 1449/PTO		<b>Complete if Known</b>	
		Application Number	10/597,199-Conf. #7625
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use as many sheets as necessary)		Filing Date	July 14, 2006
		First Named Inventor	Karsten Buse
		Art Unit	<del>NMA</del> 1792
		Examiner Name	<del>Not Yet Assigned</del> Hiteshew
Sheet	1	of	1
		Attorney Docket Number	20811/0204481-US0

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)				
/F.H./	AA*	US-3,700,912		10-24-1972	Glass et al.	
/F.H./	AB*	US-3,932,299		01-13-1976	Phillips	
/F.H./	AC*	US-4,396,246		08-02-1983	Holman	
/F.H./	AD*	US-5,902,519		05-11-1999	Stoll	
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/F.H./	AH*	US-5,904,912		05-18-1999	Kitamura et al.	

FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>3</sup>
		Country Code <sup>2</sup> -Number <sup>4</sup> -Kind Code <sup>5</sup> (if known)					
/F.H./	BA	DE-10300080		07-22-2004	Deutsche Telekom Ag		✓

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NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.		T <sup>2</sup>
/F.H./	CA	A.A. BUKHARAEV et al.: "Investigation of iron impurity centres in lithium niobate", Fizika Tverdogo Tela, USSR, Feb. 1976, ISSN 0367-3294, Soviet Physics - Solid State, USA, ISSN 0038-5654, XP-002320127 (1 page).		
/F.H./	CB	K. BUSE et al.: "Development of the thermally fixed holograms in photorefractive lithium-niobate crystals without light", Optical Materials 18 (2001), Elsevier Science B.V., pp. 17-18 (2 pages).		
/F.H./	CC	K. BUSE: "Light-induced charge transport processes in photorefractive crystals II: Materials", Applied Physics B (Lasers and Optics) Vol. 64, 1997, Springer-Verlag, pp. 391-407 (17 pages).		
/F.H./	CD	A. DHAR: "Optical properties of reduced lithium niobate single crystals", Journal of Applied Physics 68 (1990 1 December, No. 11, New York, pp. 5804-5809 (6 pages).		
/F.H./	CE	L. GALAMBOS et al.: "Doubly doped stoichiometric and congruent lithium niobate for holographic data storage", Journal of Crystal Growth 229 (2001), Elsevier Science B.V., pp. 228-232 (5 pages).		
/F.H./	CF	N. Y. KAMBER et al.: "Threshold effect of incident light intensity for the resistance against the photorefractive light-induced scattering in doped lithium niobate crystals", Optics Communications 176, 15 March 2000, Elsevier Science B.V., pp. 91-96 (6 pages).		
/F.H./	CG	T. ZHANG et al.: "Optical damage resistance of In:Fe:LiNbO <sub>3</sub> crystals related to the defect structure". Materials Letters 58 (2004). science direct, Elsevier B.V., pp. 3074-3078 (5 pages).		

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Examiner Signature	/Felisa Hiteshew/	Date Considered	01/18/2008
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